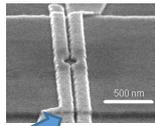


THE ROBUSTNESS AND UNIVERSALITY OF TUNABLE-BARRIER ELECTRON PUMPS

S. P. Giblin¹, P. See¹, J. D. Fletcher¹, J. P. Griffiths², G. A. C. Jones², I. Farrer², D. A. Ritchie², M. -H. Bae³, Y. -H. Ahn^{3,4}, M. Seo^{3,5}, Y. Chung⁵, N. Kim³, G. Yamahata³, T. Karasawa⁶, A. Fujiwara⁶, R. Zhao⁷, A. Rossi², F. E. Hudson⁷, M. Möttönen⁸, A. Dzurak⁷, T. J. B. M. Janssen¹ and M. Kataoka¹

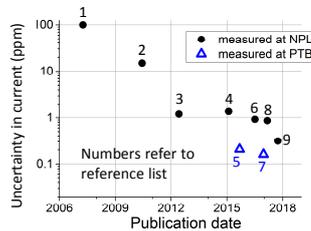
¹National Physical Laboratory, Hampton Road, Teddington, Middlesex, TW11 0LW, United Kingdom, ²Cavendish Laboratory, University of Cambridge, JJ Thomson Avenue, Cambridge CB30HE, United Kingdom, ³Korea Research Institute of Standards and Science, Daejeon 34113, Republic of Korea, ⁴Department of Physics, Korea University, Seoul 136-713, Republic of Korea, ⁵Department of Physics, Pusan National University, Busan 609-735, Republic of Korea, ⁶NTT Basic Research Laboratories, NTT Corporation, 3-1 Morinosato Wakamiya, Atsugi, Kanagawa 243-0198, Japan, ⁷School of Electrical Engineering and Telecommunications, University of New South Wales, Sydney, New South Wales 2052, Australia, ⁸QCD Labs, COMP Centre of Excellence, Department of Applied Physics, Aalto University, 00076 AALTO, Finland

1. The tunable-barrier electron pump



The semiconductor tunable-barrier electron pump is a candidate for a **primary current standard**. It generates a current by moving electrons one at a time in response to a periodic control voltage at frequency f . Electron pump research has driven dramatic improvements in small current metrology (graph at right, refs 3 and 10).

Below: modulation of electrostatic potential barriers to pump one electron.

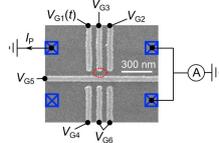


2. Pumps measured at NPL

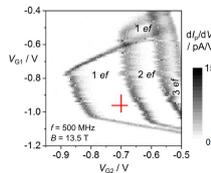
SEM image	Fabrication Institute	Material	Number of control gate voltages	References
	UNIVERSITY OF CAMBRIDGE	GaAs	2	[3]
	KRISS	GaAs	6 (2 gates connected)	[4,8]
	UNSW	Si	7	[9]
	NTT	Si	3 (including top gate)	[6]

Panel 4 also summarises precision measurements made at PTB, on PTB-designed GaAs pumps – see refs. 5 and 7.

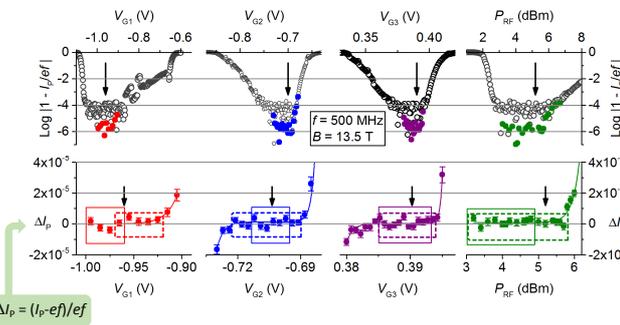
3. Robustness



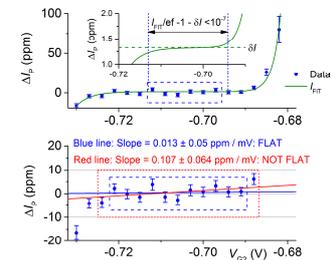
Below: Pump map. Cross indicates optimal working point



We can change any of the control parameters of the KRISS pump: V_{G1} , V_{G2} , V_{G3} or P_{RF} **without changing the pump current**, within an uncertainty of around 2 ppm per data point. Data in this panel taken from ref. [8]. See also ref. [7] for another robustness study.



A **plateau** can be defined with respect to a fit - in this case, a sum of two exponentials [ref. 11] with an offset δI . Alternatively, linear fits can establish a range of data where the slope is less than the fitting uncertainty.



4. Universality

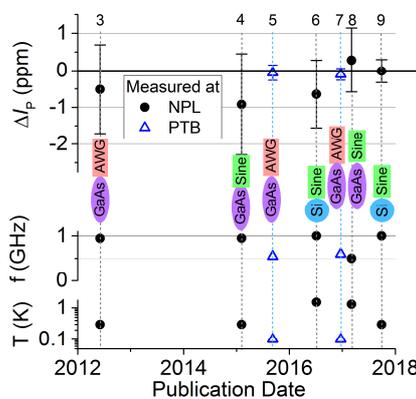
Does the pump mechanism work in pumps made from different materials, with different designs?

For 7 studies on optimally tuned electron pumps at NPL and PTB, we plot:

- Pump current ΔI_p
- Drive frequency f
- cryostat temperature T

Also indicated are the material used to make the pump (Si or GaAs) and whether the drive signal was a Sine Wave or from an Arbitrary Waveform Generator (AWG).

Numbers along the top of the plot refer to the reference list



5. Conclusions

Robustness:

We have shown robustness at the 1-2 ppm level of one design of pump to changes in 4 parameters; 3 gate voltage and the RF drive power.

Universality:

We have measured **4 different designs of pump**, 2 each using GaAs and Si technology. They all have current equal to ef within uncertainty of 1 ppm or less when optimally tuned. Our best measurement, **0.27 ppm on a silicon pump @ 1 GHz**, can be compared with the best measurement on a GaAs pump, **0.16 ppm @ 600 MHz**, ref. 7.

Next:

Direct comparison of two different pumps. Guidelines for electron pumps as primary realisation of ampere.

References:

- [1] M. D. Blumenthal et al, *Nature Physics* **3**, 343 (2007).
- [2] S. P. Giblin et al, *New Journal of Physics* **12**, 073013 (2010)
- [3] S. P. Giblin et al, *Nature Communications* **3**, 930 (2012)
- [4] M. -H Bae et al, *Metrologia* **52**, 195 (2015)
- [5] F. Stein et al, *Appl. Phys. Lett.* **107**, 103501 (2015)
- [6] G. Yamahata et al, *Appl. Phys. Lett.* **109**, 013101 (2016).
- [7] F. Stein et al, *Metrologia*, S1 (2016)
- [8] S. P. Giblin et al, *Metrologia* **54**, 299 (2017)
- [9] R. Zao et al, arXiv: 1703-04795, Submitted to *Physical Review Applied*
- [10] D. Drung et al, *Review of Scientific Instruments* **84**, 024703 (2015)
- [11] V. Kashcheyevs and J. Timoshenko, *Conference on Precision Electromagnetic Measurements* 536 (2014)